CLAIMS

1. A polyvinyl acetal resin for heat-developable photosensitive materials

which is a polyvinyl acetal resin synthesized by the acetalization reaction between a polyvinyl alcohol and an aldehyde and

which comprises having a degree of polymerization of 200 to 3,000, a residual acetyl group content of 0 to 25 mole percent and a residual hydroxyl group content of 17 to 35 mole percent, as calculated while regarding one acetal group as two acetalized hydroxyl groups, a water content of not more than 2.5% by weight and a residual aldehyde content of not more than 10 ppm and is free of any antioxidant.

2. A polyvinyl acetal resin for heat-developable photosensitive materials

which comprises two polyvinyl acetal resin species differing in degree of polymerization by at least 300 and

which comprises having an apparent degree of polymerization of 200 to 1,000, an apparent residual acetyl group content of 0 to 25 mole percent and an apparent residual hydroxyl group content of 17 to 35 mole percent, as calculated while regarding one acetal group as two acetalized hydroxyl groups, a water content of not more than 2.5% by weight and a residual aldehyde content of not more than 10 ppm and is free of any antioxidant.

3. The polyvinyl acetal resin for heat-developable photosensitive materials according to Claim 1 or 2,

which comprises having a glass transition temperature of 55 to 110°C.

4. A heat-developable photosensitive material

in which the polyvinyl acetal resin for heat-developable photosensitive material according to any of Claims 1 to 3 is

used.